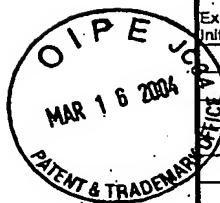


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| Substitute for form 1449A/PTO | | Complete If Known | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | Application Number | 10,724,113 |
| (use as many sheets as necessary) | | Filing Date | December 1, 2003 |
| | | First Named Inventor | Moshe FINAROV et al. |
| | | Group Art Unit | -207 2886 |
| | | Examiner Name | - R. Punnoose |
| Sheet | 1 | of | 1 |
| | | Attorney Docket Number | FINAROV=3A |



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**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

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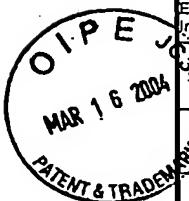
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| Application Number | 10,724,113 |
| Filing Date | December 1, 2003 |
| First Named Inventor | Moshe FINAROV et al. |
| Group Art Unit | 267 2886 |
| Examiner Name | - R. Punnoose |
| Attorney Docket Number | FINAROV=3A |

**OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS**

| Examiner Initials* | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published | T ² |
|--------------------|-----------------------|------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|----------------|
| RP | AH | N. CHATEAU et al, "Algorithm for the rigorous coupled-wave analysis of grating diffraction", <i>Journal of the Optical Society of America A</i> , vol. 11, no. 4, April 1994, pp 1321-1331 | |
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Examiner Signature

/Roy Punnoose/

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PTO/SB/08A (10-86)

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| Substitute for form 1449A/PTO | | Complete if Known | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | Application Number | 09/610,889 |
| (use as many sheets as necessary) | | Filing Date | July 6, 2000 |
| | | First Named Inventor | FINAROV et al. |
| | | Group Art Unit | 297 2886 |
| | | Examiner Name | R. Punnoose |
| Sheet | 1 | of | 2 |
| | | Attorney Docket Number | FINAROV-3 |

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| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | | | Application Number | 09/610,889 |
| (use as many sheets as necessary) | | | | Filing Date | July 6, 2000 |
| Sheet | 2 | of | 2 | First Named Inventor | FINAROV et al. |
| | | | | Group Art Unit | 267 2886 |
| | | | | Examiner Name | R. Punnoose |
| | | | | Attorney Docket Number | FINAROV=3 |

| OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS | | | | | |
|---------------------------------------------------|-----------------------|--------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|--|--|----------------|
| Examiner Initials* | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published | | | |
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| | | First Named Inventor | Moshe FINAROV |
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| Sheet | 1 | of | 1 |

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